

List of reference symbols

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|----|----|-----------------------------|
| | 1 | semiconductor substrate |
| | 2 | first trench |
| 5 | 3 | oxidized silicon layer |
| | 4 | aluminium-oxide layer |
| | 5 | horizontal regions |
| | 6 | second trench |
| | 7 | widened second trench |
| 10 | 8 | bottle structure |
| | 9 | first electrode |
| | 10 | dielectric layer |
| | 11 | conductive filling |
| | 12 | rugged polysilicon layer |
| 15 | 13 | first silicon nitride layer |
| | 14 | silicon nitride layer |
| | 15 | hardmask |
| | 16 | process window |